

Supporting Information

Hypercoordinated Si/Ge Driving Excellent HER Catalytic Performance in New TM₂X (X = Si and Ge) Monolayers: A High-Throughput Investigation by Screening Transition Metal Elements

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1. Supporting Figures

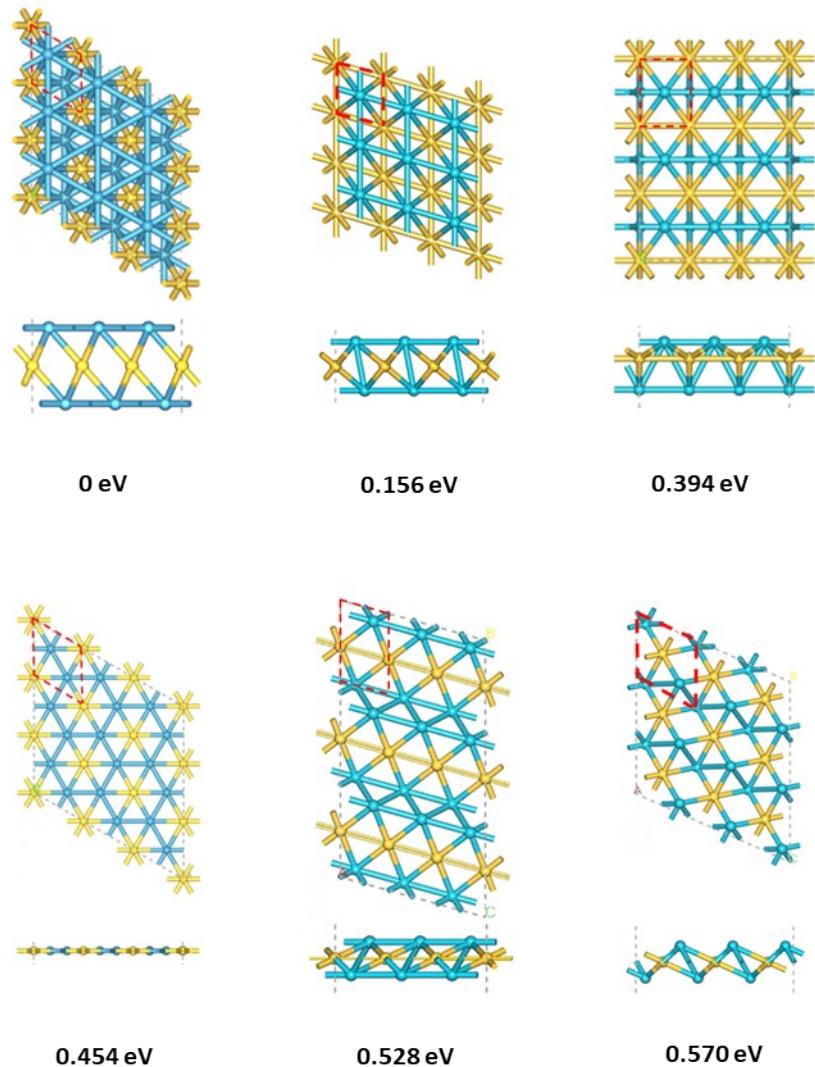


Figure S1. Possible 2D Co₂Si structures obtained through the PSO simulation implemented in CALYPSO code. The relative energy per atom is indicated.

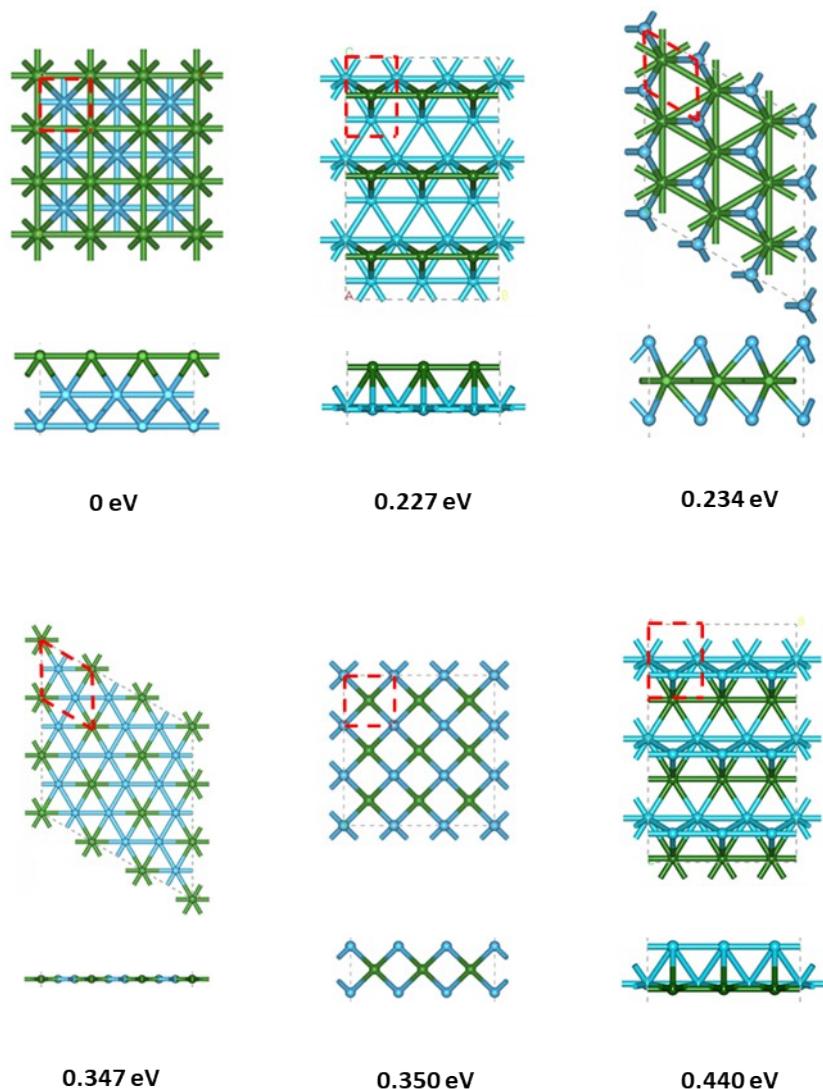


Figure S2. Possible 2D Co₂Ge structures obtained through the PSO simulation implemented in CALYPSO code. The relative energy per atom is indicated.

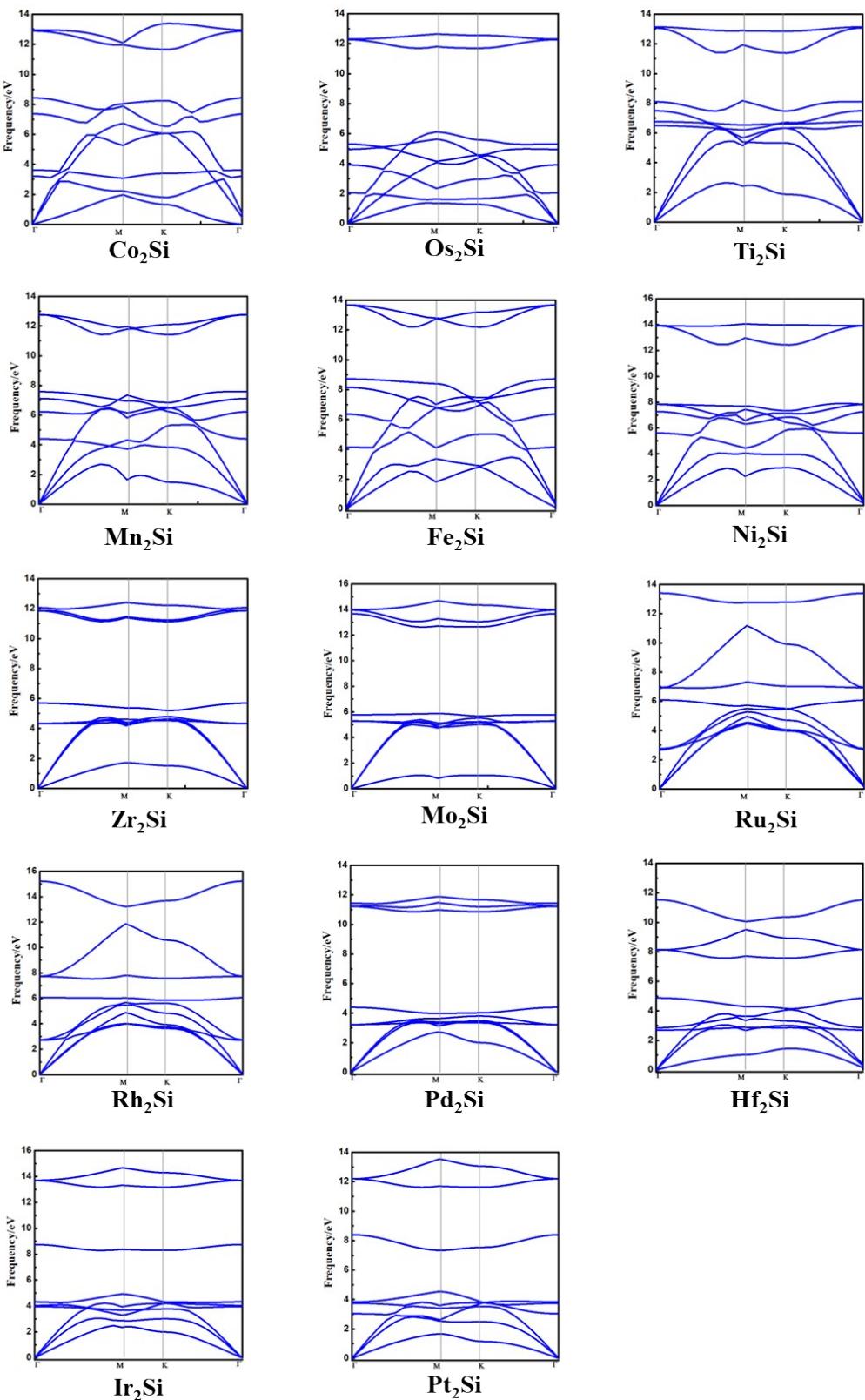


Figure S3. Phonon spectrum of the TM_2Si series.

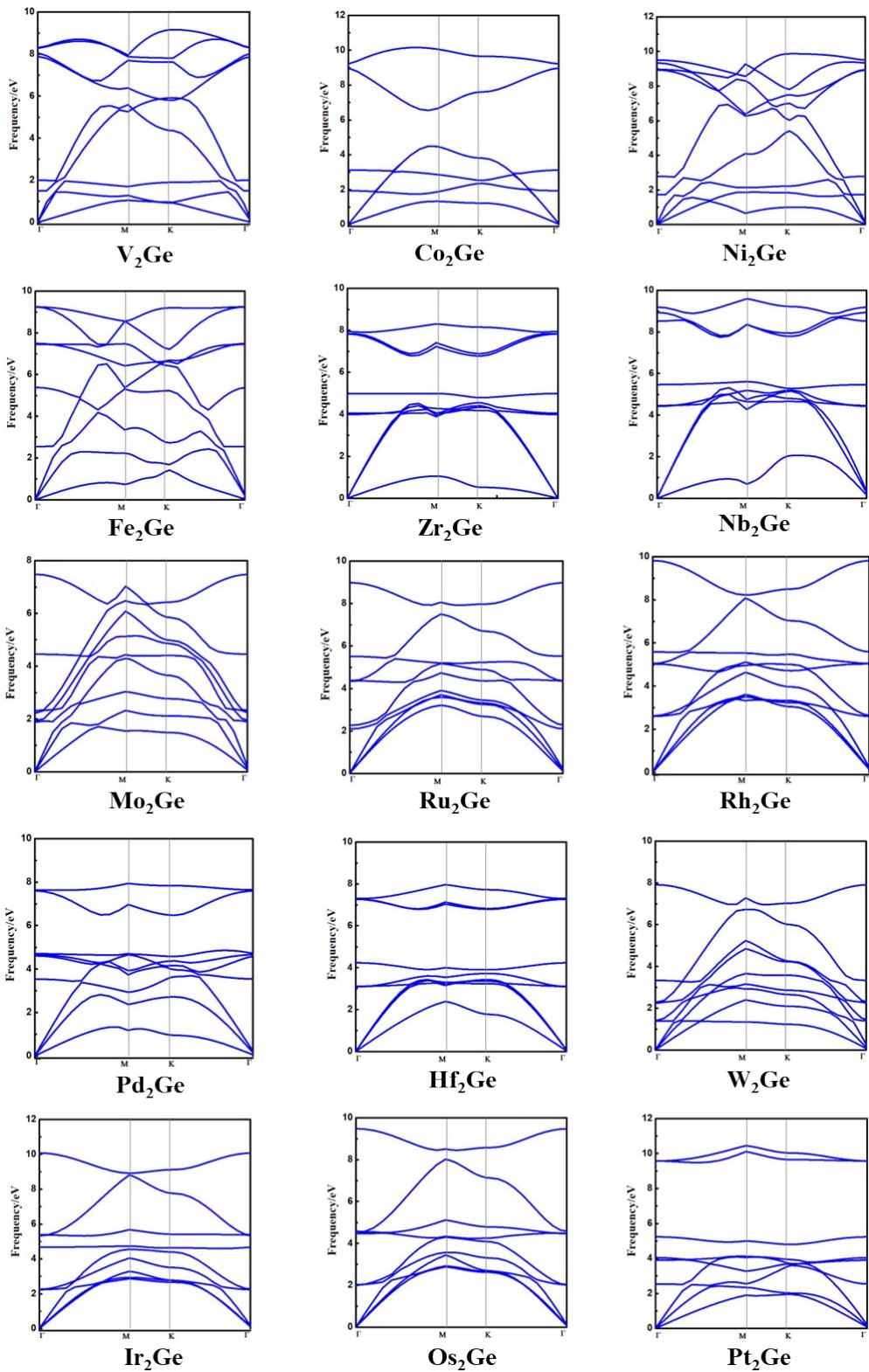


Figure S4. Phonon spectrum of the TM₂Ge series.

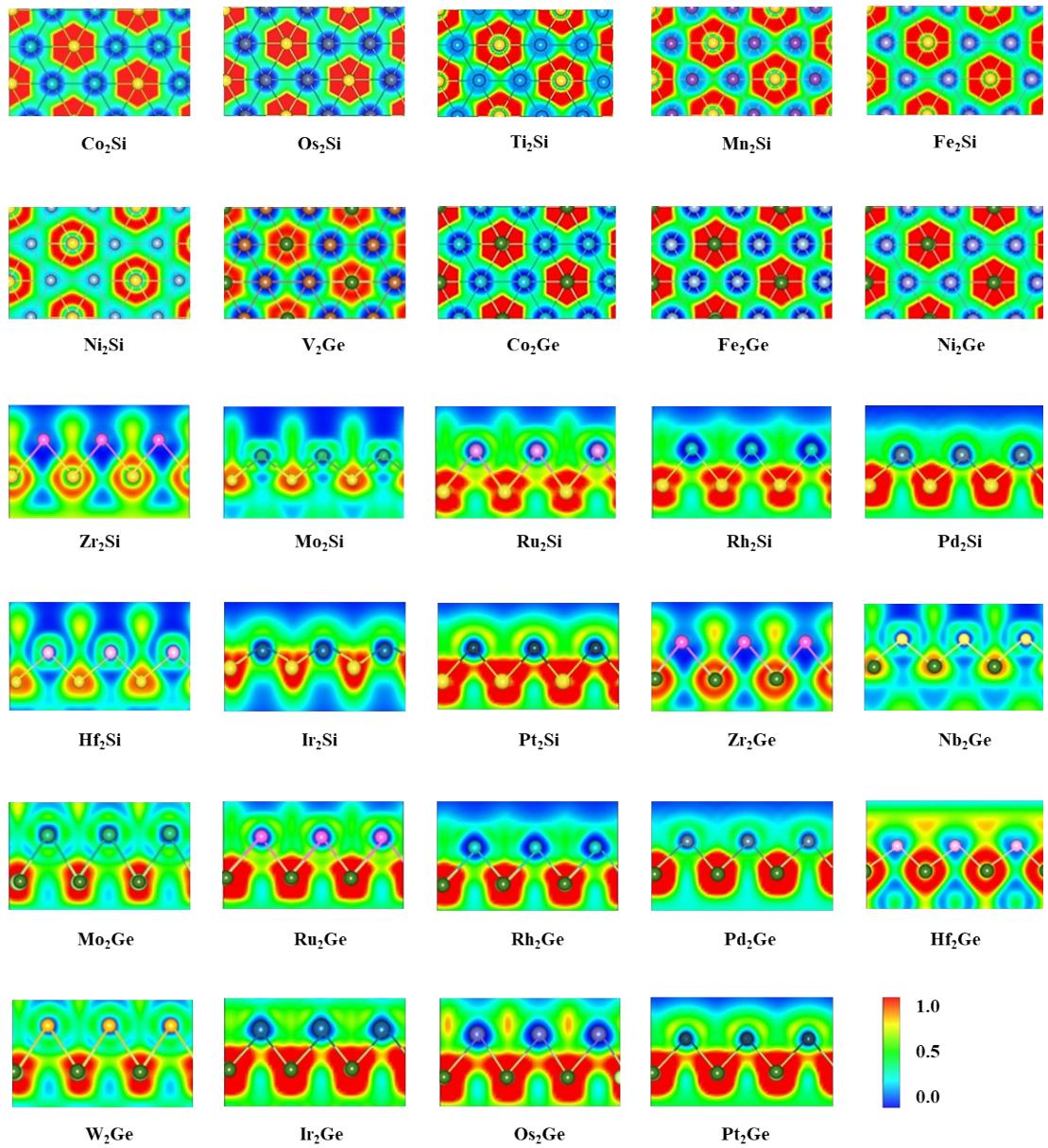


Figure S5. ELF maps of the TM₂X (X=Si and Ge) systems, where the pictures in the first two rows are the top views of the planar and quasi-planar monolayers, and the others are the side views of the buckled monolayers.

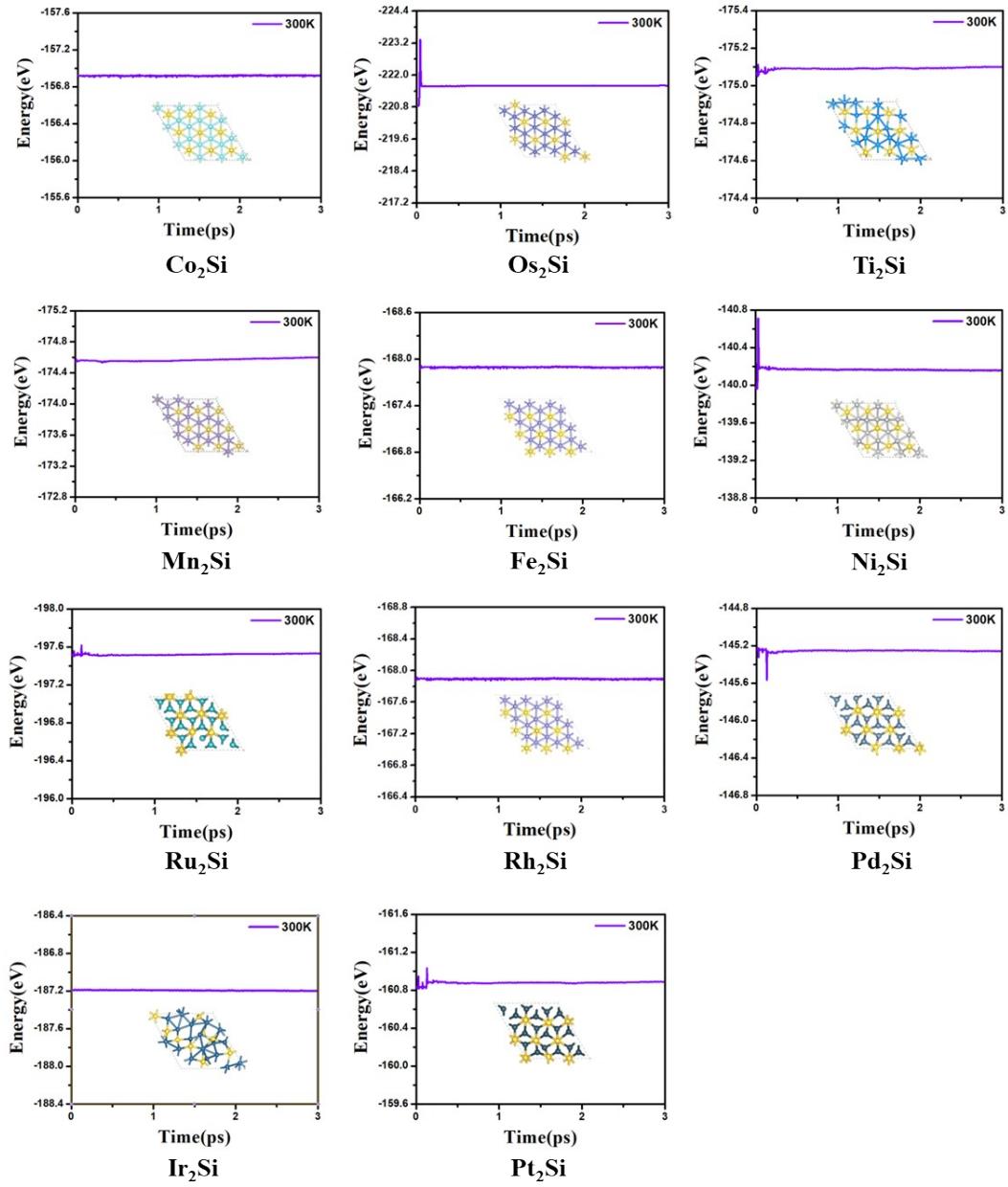


Figure S6. Evolution of total energy of the TM₂Si monolayers at 300 K from AIMD, and the corresponding snapshots after 3 ps.

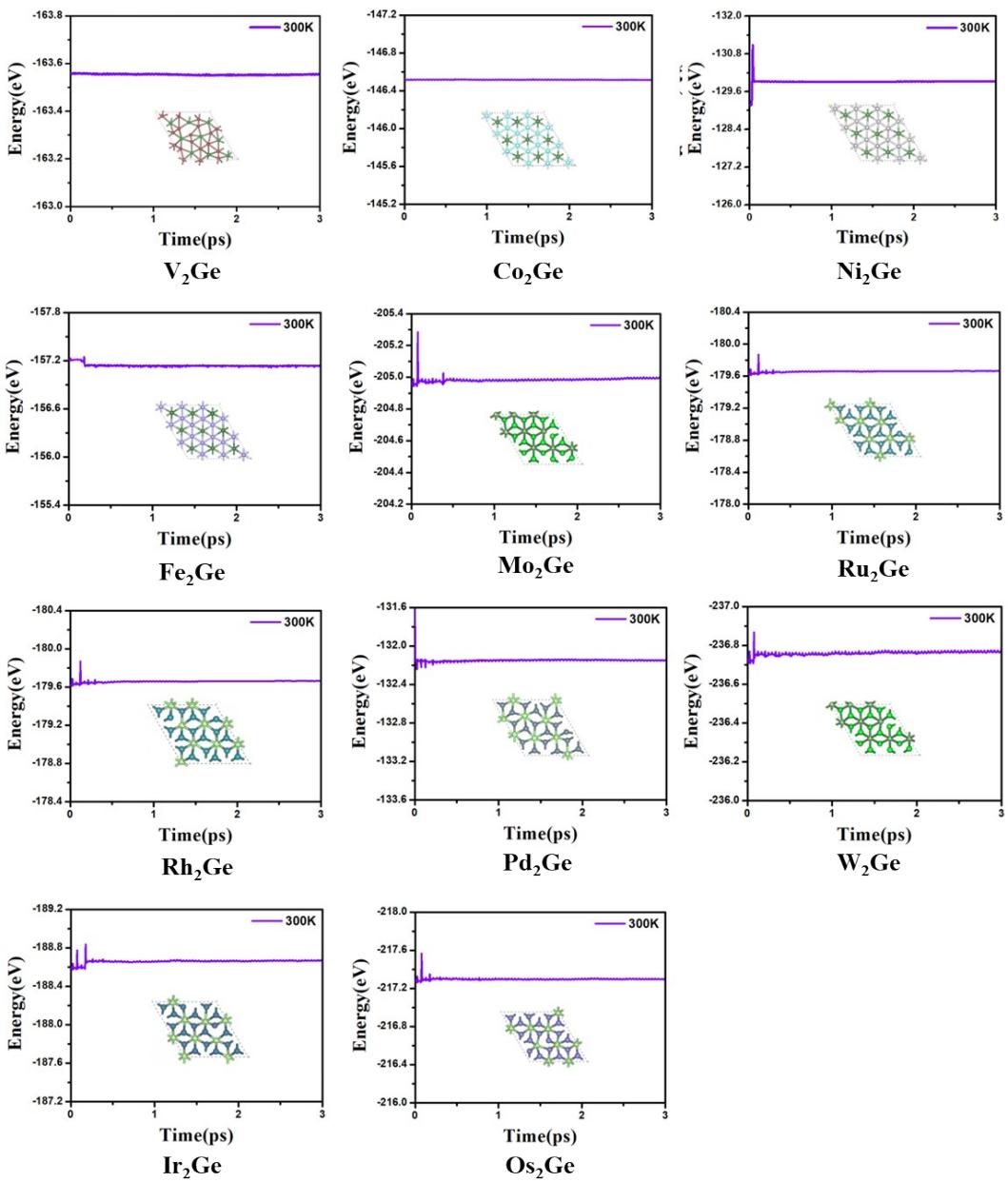


Figure S7. Evolution of total energy of the TM₂Ge monolayers at 300 K from AIMD, and the corresponding snapshots after 3 ps.

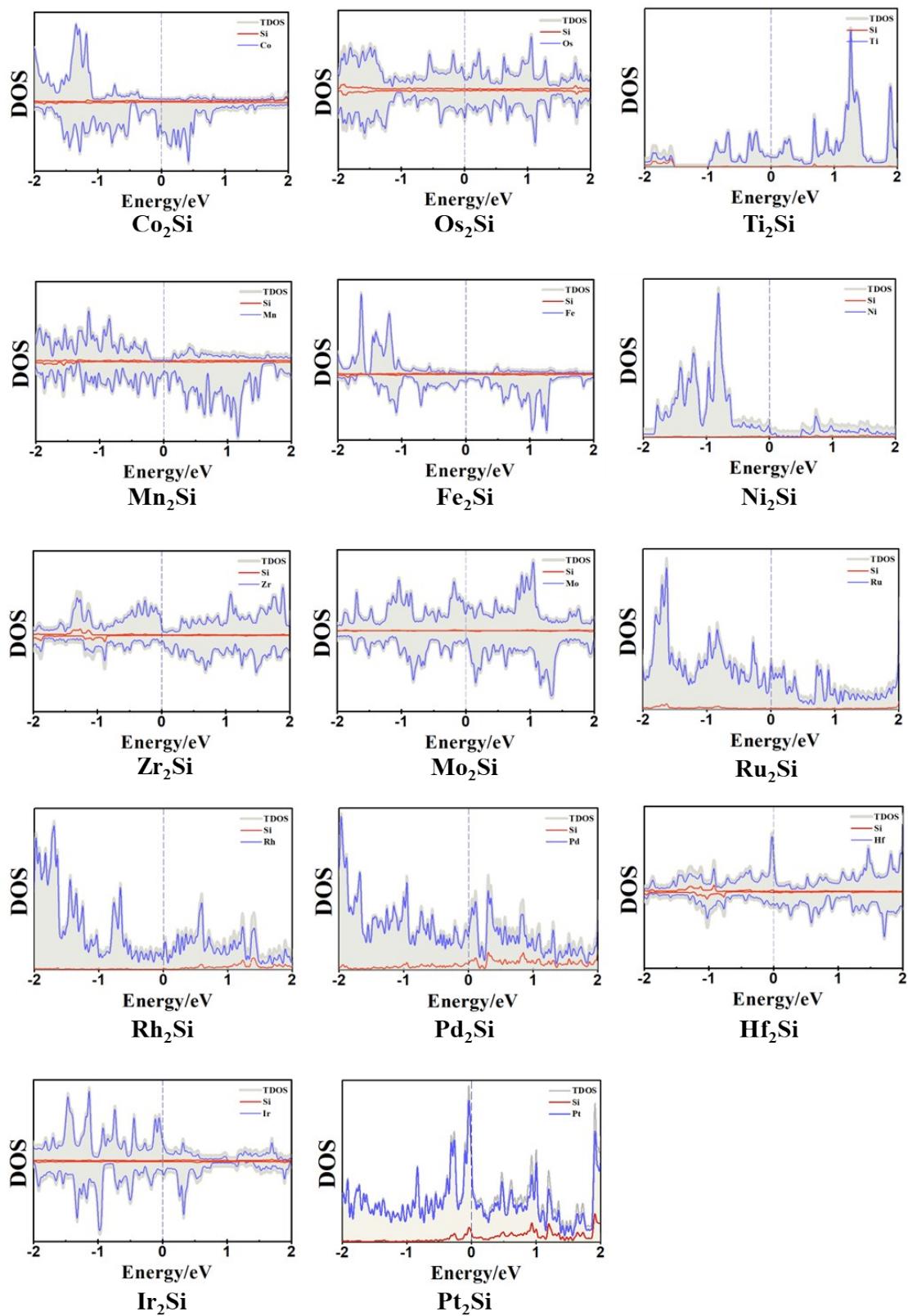


Figure S8. The calculated DOSs of the TM_2Si systems.

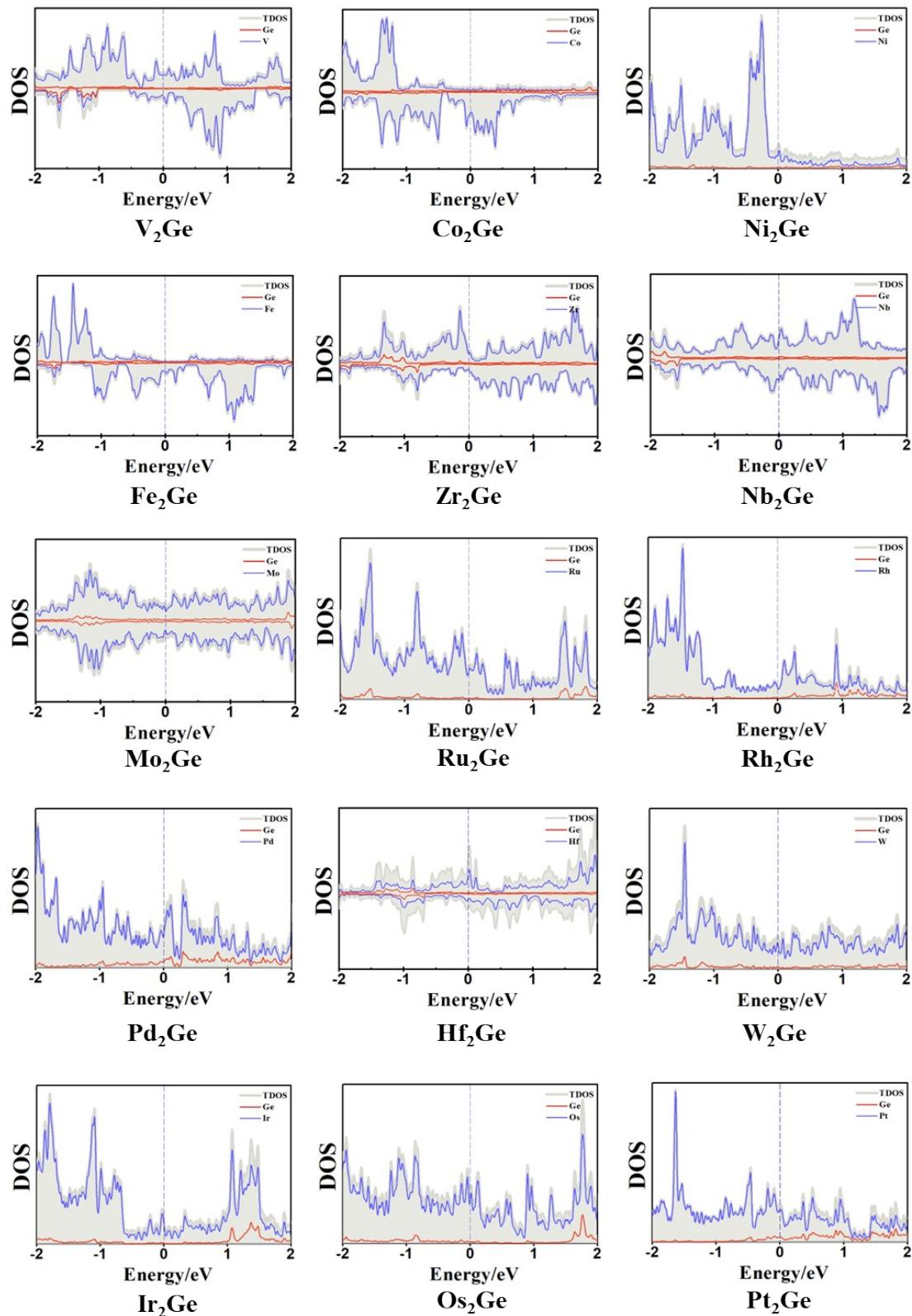


Figure S9. The calculated DOSs of the TM_2Ge systems.

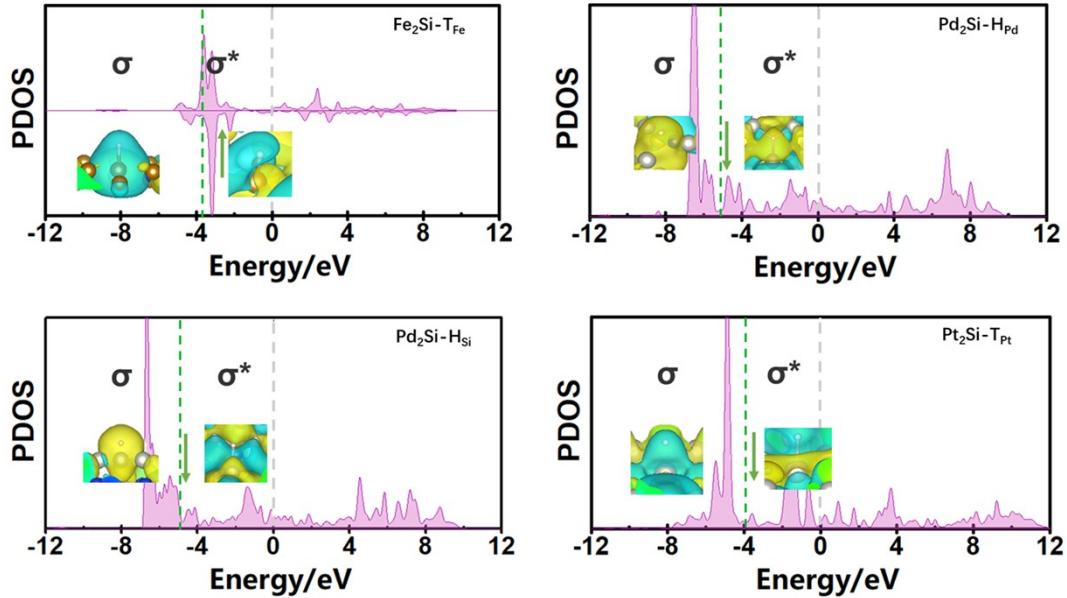


Figure S10. Partial density of states (PDOS) about the 1s orbital of H atom after the H adsorption of TM₂Si (TM=Fe, Pd and Pt). The Fermi level is set to zero marked by the gray dashed line. Inset: molecular orbitals related to the H atom adsorbed at the active site in different energy ranges marked by the green dashed line. The green arrow represents the σ_{1s} -center of the adsorbed H.

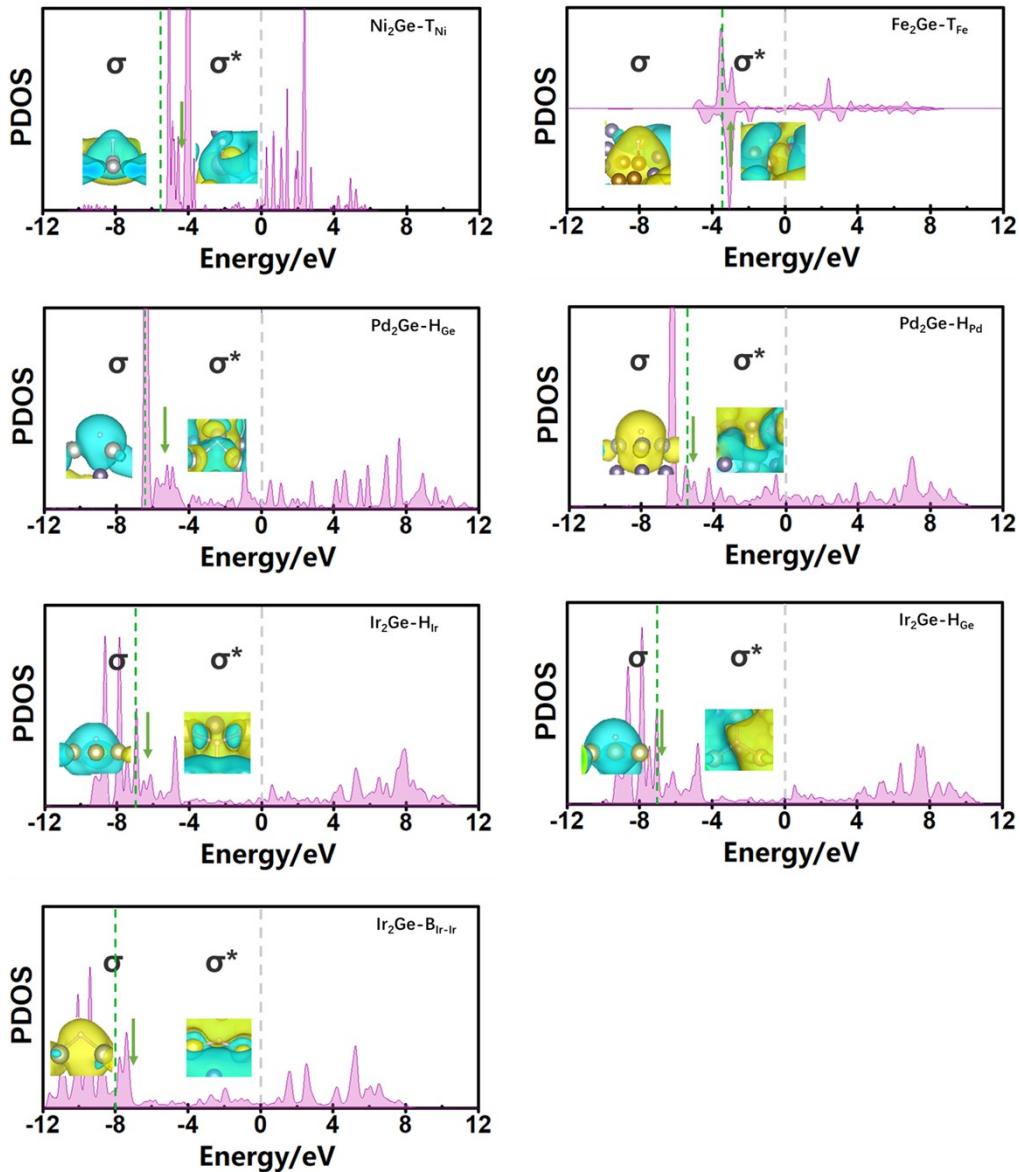


Figure S11. Partial density of states (PDOS) about the 1s orbital of H atom after the H adsorption of TM_2Ge ($\text{TM}=\text{Ni}, \text{Fe}, \text{Pd}$ and Ir). The Fermi level is set to zero marked by the gray dashed line. Inset: molecular orbitals related to the H atom adsorbed at the active site in different energy ranges marked by the green dashed line. The green arrow represents the σ_{1s} -center of the adsorbed H.

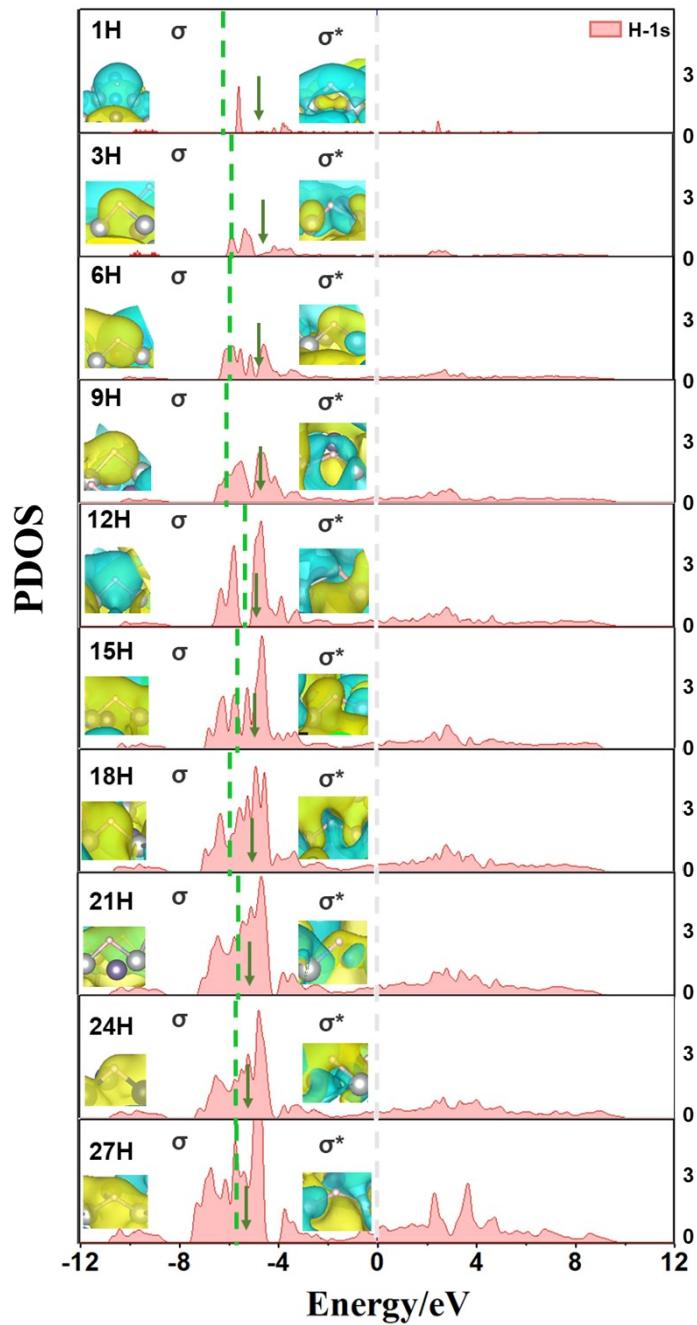


Figure S12. PDOS about the 1s orbitals of H atoms as well as the σ_{1s} -center for H adsorbed on the Ni₂Ge monolayer under the different H coverages. The Fermi level is set to zero marked by the gray dashed line. Inset: Molecular orbitals related to the H atom adsorbed at the active site in different energy ranges marked by the green dashed line. The green arrow represents the σ_{1s} -center of the adsorbed H.

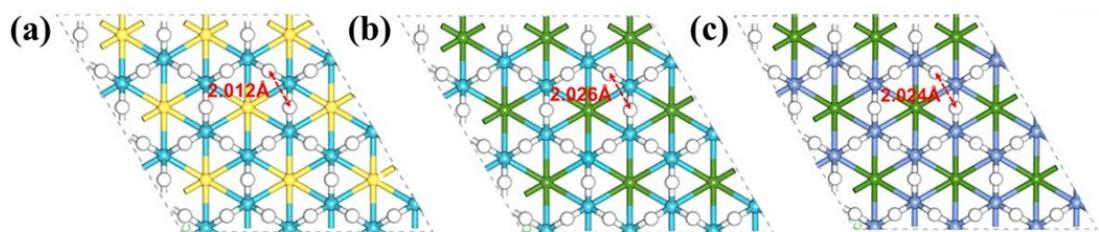


Figure S13. The calculated distance between two adjacent H atoms on the 2D Co₂Si (a), Co₂Ge (b), and Ni₂Ge (c) monolayers at the highest hydrogen coverage ($\theta_{H^*} = 3$ ML).

2. Supporting Tables

Table S1. The solvent effect on the computed ΔG_{H^*} values of the sampled Co₂Si monolayer.

Adsorption sites	ΔG_{H^*} (eV) without solvation	ΔG_{H^*} (eV) with solvation
B _{Co-Co}	-0.076	-0.077
T _{Co}	0.101	0.110
T _{Si}	0.346	0.357

Table S2. The calculated ΔG_{H^*} values of 2D Co₂Si and Co₂Ge monolayers under the DFT+U method.

Adsorption sites	Co ₂ Si		Co ₂ Ge	
	ΔG_{H^*} (eV) without U _{eff}	ΔG_{H^*} (eV) with U _{eff}	ΔG_{H^*} (eV) without U _{eff}	ΔG_{H^*} (eV) with U _{eff}
B _{Co-Co}	-0.076	-0.120	-0.083	-0.099
T _{Co}	0.101	0.052	0.095	0.074
T _{Si/Ge}	0.346	0.329	0.604	0.574

Table S3. Structural information of the predicted TM₂Si monolayers, including the lattice parameters (a and b), bond lengths, and buckled heights (h).

Systems	a=b (Å)	Bond Lengths (Å)		h (Å)
		TM-TM	TM-Si	
Planar	Co₂Si	4.005	2.309	2.309
	Os₂Si	3.486	2.460	2.460
Quasi-planar	Ti₂Si	3.933	2.925	2.451
	Mn₂Si	3.890	2.668	2.358
Buckled	Fe₂Si	3.931	2.418	2.308
	Ni₂Si	3.780	2.526	2.215
	Zr₂Si	3.600	(3.681)	2.574
	Mo₂Si	3.409	(3.253)	2.356
	Ru₂Si	2.715	(3.976)	2.407
	Rh₂Si	2.800	(3.819)	2.368
	Pd₂Si	3.190	(3.553)	2.387
	Hf₂Si	3.600	(3.692)	2.578
	Ir₂Si	3.560	(2.970)	2.318
	Pt₂Si	2.985	(3.722)	2.385
				3.299

Table S4. Structural information of the predicted TM₂Ge monolayers, including the lattice parameters (a and b), bond lengths, and buckled heights (h).

Systems	a=b (Å)	Bond Lengths (Å)		h (Å)
		TM-TM	TM-Si	
Planar	V₂Ge	4.450	2.569	2.569
	Co₂Ge	4.078	2.355	2.355
	Ni₂Ge	4.105	2.349	2.349
Quasi-planar	Fe₂Ge	4.051	2.456	2.369
	Zr₂Ge	3.630	(3.771)	2.610
	Nb₂Ge	3.490	(3.557)	2.492
	Mo₂Ge	2.750	(4.662)	2.706
	Ru₂Ge	2.770	(4.154)	2.496
	Rh₂Ge	2.880	(3.951)	2.450
	Pd₂Ge	3.143	(3.816)	2.472
	Hf₂Ge	3.602	(3.773)	2.607
	W₂Ge	2.750	(4.646)	2.695
Buckled	Os₂Ge	2.754	(4.189)	2.507
	Ir₂Ge	2.835	(3.999)	2.451
	Pt₂Ge	3.050	(3.863)	2.461
				3.438

Table S5. The TM-TM and TM-Si bond lengths in TM_2Si , as well as in the relevant material systems synthesized experimentally.

Systems	Bond Lengths (\AA)					
	TM-TM			TM-Si		
	In this study	In relevant experimental materials	In this study	In relevant experimental materials		
Planar	Co_2Si	2.309	2.470	Co	2.309	2.488
	Os_2Si	2.460	2.682	Os	2.460	2.554
Quasi-planar	Ti_2Si	2.925	2.936	Ti	2.451	2.547
	Mn_2Si	2.668	2.750	Mn	2.358	2.529
	Fe_2Si	2.418	2.585	Fe	2.308	2.766
	Ni_2Si	2.526	2.630	TiNi(TiCo)	2.215	2.332
Buckled	Zr_2Si	--	--	--	2.574	2.778
	Mo_2Si	--	--	--	2.356	2.605
	Ru_2Si	--	--	--	2.407	2.412
	Rh_2Si	--	--	--	2.368	2.483
	Pd_2Si	--	--	--	2.387	2.488
	Hf_2Si	--	--	--	2.578	2.750
	Ir_2Si	--	--	--	2.318	2.393
	Pt_2Si	--	--	--	2.385	2.421
						Pt_2Si_3

Table S6. The TM-TM and TM-Ge bond lengths in TM_2Ge , as well as in the relevant material systems synthesized experimentally.

Systems		Bond Lengths (\AA)					
		TM-TM		TM-Ge		In this study	In relevant experimental materials
		In this study	In relevant experimental materials	In this study	In relevant experimental materials		
	V_2Ge	2.569	2.583	V	2.569	2.650	V_3Ge
Planar	Co_2Ge	2.355	2.470	Co	2.355	2.372	Co_5Ge_7
	Ni_2Ge	2.349	2.496	Ni_3Ge	2.349	2.496	Ni_3Ge
Quasi-planar	Fe_2Ge	2.456	2.482	$\text{Fe}_{13}\text{Ge}_3$	2.369	2.511	$\text{Fe}_{13}\text{Ge}_3$
	Zr_2Ge	--	--	--	2.610	2.861	ZrGeIr
Buckled	Nb_2Ge	--	--	--	2.492	2.910	Nb_3Ge
	Mo_2Ge	--	--	--	2.706	2.710	Mo_3Ge
	Ru_2Ge	--	--	--	2.496	2.444	ScRuGe_2
	Rh_2Ge	--	--	--	2.450	2.468	RhGe
	Pd_2Ge	--	--	--	2.472	2.453	TiPdGe
	Hf_2Ge	--	--	--	2.607	2.755	HfGe_2
	W_2Ge	--	--	--	2.695	2.700	WGe_2
	Os_2Ge	--	--	--	2.507	2.510	OsGe_2
	Ir_2Ge	--	--	--	2.451	2.502	ZrIrGe
	Pt_2Ge	--	--	--	2.461	2.462	PtGeS

Table S7. The calculated elastic coefficients of the TM₂Si monolayers.

Systems	C ₁₁ =C ₂₂	C ₁₂	C ₆₆
Ti₂Si	135.588	114.969	10.314
Mn₂Si	248.812	64.710	92.051
Fe₂Si	489.270	207.126	140.653
Co₂Si	134.790	54.386	40.176
Ni₂Si	281.647	5.152	138.247
Zr₂Si	372.698	168.653	102.022
Mo₂Si	473.650	71.769	200.941
Ru₂Si	1296.801	477.474	409.663
Pd₂Si	106.312	15.037	45.637
Hf₂Si	607.575	190.661	208.456
Ir₂Si	472.927	261.131	105.898
Pt₂Si	254.809	31.293	111.758

Table S8. The calculated elastic coefficients of the TM₂Ge monolayers.

Systems	C ₁₁ =C ₂₂	C ₁₂	C ₆₆
V ₂ Ge	449.825	173.187	138.319
Fe ₂ Ge	363.835	198.101	82.867
Co ₂ Ge	110.082	43.175	32.537
Ni ₂ Ge	476.347	341.836	67.256
Zr ₂ Ge	258.205	147.002	55.602
Nb ₂ Ge	353.544	192.171	80.686
Ru ₂ Ge	1220.584	365.860	427.362
Rh ₂ Ge	602.608	169.360	216.624
Hf ₂ Ge	610.430	181.581	224.425
Os ₂ Ge	1462.744	835.523	313.610
Ir ₂ Ge	1203.100	321.130	440.985
Pt ₂ Ge	63.245	42.958	10.644

Table S9. The computed ΔG_{H^*} values for TM₂Si systems. The symbol “--” indicates that structures with adsorbed H* cannot be obtained.

Systems	Adsorption sites	ΔG_{H^*} (eV)
Ti₂Si		--
Mn₂Si		--
Fe₂Si	T _{Fe1}	0.242
Co₂Si	T _{Si}	0.346
	T _{Co}	0.101
	B _{Co-Co}	-0.076
Ni₂Si		--
Zr₂Si	H _{Zr}	-1.068
	H _{Si}	-1.018
Mo₂Si		--
Ru₂Si	H _{Ru}	-0.415
	T _{Ru}	-0.390
Rh₂Si		--
Pd₂Si	H _{Pd}	0.076
	H _{Si}	0.246
Hf₂Si	H _{Hf}	-0.847
	H _{Si}	-1.094
Os₂Si	T _{Si}	-0.780
	T _{Os}	-1.351
Ir₂Si		--
Pt₂Si	T _{Pt}	0.203
	H _{Pt}	0.328
	B _{Pt-Pt}	0.292

Table S10. The computed ΔG_{H^*} values for $T M_2 Ge$ systems. The symbol “--” indicates that structures with adsorbed H^* cannot be obtained.

Systems	Adsorption sites	ΔG_{H^*} (eV)
V₂Ge	B _{V-V}	-0.504
Fe₂Ge	T _{Fe1}	0.175
	T _{Fe2}	-0.197
	B _{Fe-Fe}	-0.293
Co₂Ge	T _{Ge}	0.604
	T _{Co}	0.095
	B _{Co-Co}	-0.083
Ni₂Ge	T _{Ge}	0.551
	T _{Ni}	0.207
	B _{Ni-Ni}	-0.333
Zr₂Ge	H _{Zr}	-1.362
	H _{Ge}	-1.346
Nb₂Ge	--	
Mo₂Ge	H _{Mo}	-1.129
	H _{Ge}	-1.644
Ru₂Ge	H _{Ru}	0.881
	T _{Ru}	-0.468
Rh₂Ge	T _{Rh}	-0.984
	H _{Rh}	-1.498
	H _{Ge}	-1.369
Pd₂Ge	H _{Pd}	0.002
	H _{Ge}	0.120
Hf₂Ge	H _{Hf}	-1.309
	H _{Ge}	-1.572
W₂Ge	T _W	-1.183
	H _W	-0.693
	H _{Ge}	-0.726
Os₂Ge	H _{Os}	-0.754
Ir₂Ge	T _{Ir}	0.351
	H _{Ir}	0.152
	H _{Ge}	0.212
	B _{Ir-Ir}	0.218
Pt₂Ge	--	

Table S11. The σ_{1S} centers for H adsorption on TM₂Si (TM=Co, Fe, Pd and Pt) monolayers.

Systems	Adsorption sites	σ_{1S} centers (eV)
Co₂Si	T _{Co}	-4.026
	B _{Co-Co}	-4.855
Fe₂Si	T _{Fe1}	-3.255
Pd₂Si	H _{Pd}	-4.888
	H _{Si}	-4.870
Pt₂Si	T _{Pt}	-3.816

Table S12. The σ_{1S} centers for H adsorption on TM₂Ge (TM=Co, Ni, Fe, Pd and Ir) monolayers.

Systems	Adsorption sites	σ_{1S} centers (eV)
Co₂Ge	T _{Co}	-3.994
	B _{Co-Co}	-4.778
Ni₂Ge	T _{Ni}	-4.323
Fe₂Ge	T _{Fe1}	-3.192
Pd₂Ge	H _{Pd}	-5.104
	H _{Ge}	-5.116
Ir₂Ge	H _{Ir}	-6.285
	H _{Ge}	-6.918
	B _{Ir-Ir}	-7.005

Table S13. The σ_{1S} centers for H adsorption on the Co₂Si, Co₂Ge and Ni₂Ge monolayers under the different H coverage.

n	σ_{1S} centers (eV)		
	Co₂Si	Co₂Ge	Ni₂Ge
1	-4.855	-4.778	-4.840
3	-4.708	-4.774	-4.745
6	-4.881	-4.679	-4.918
9	-5.062	-4.669	-4.866
12	-4.984	-4.820	-4.910
15	-4.959	-4.770	-5.066
18	-4.935	-4.788	-5.107
21	-5.062	-4.916	-5.210
24	-5.281	-5.073	-5.268
27	-5.407	-5.167	-5.475